## **AMENDMENTS TO THE CLAIMS**

The following listing of claims will replace all prior versions and listings of claims in the application.

## **LISTING OF CLAIMS**

- 1. (previously amended) A liquid crystal device comprising:
- a first substrate;
- a second substrate disposed so as to oppose the first substrate;
- a color layer provided on the first substrate;
- an insulating film provided on the color layer and comprising at least one of  $Ta_2O_5$ ,  $ZrO_2$ , and  $TiO_2$  as a primary component; and
- a conductive film having a property of transmitting light provided on the insulating film.
- 2. (previously amended) A liquid crystal device according to Claim 1, wherein, when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 3. (previously amended) A liquid crystal device according to Claim 2, wherein  $\lambda$  is 550 nm.
- 4. (previously amended) A liquid crystal device according to Claim 1, further comprising a transparent resin film between the color layer and the insulating film.

- 5. (previously amended) A liquid crystal device according to Claim 1, further comprising a reflective film between the color layer and the first substrate.
- 6. (previously amended) A liquid crystal device according to Claim 1, further comprising an underlying layer provided on the second substrate and composed of a material substantially identical to that for the insulating film, and an active element provided on the underlying layer.
- 7. (previously amended) A liquid crystal device according to Claim 5, wherein the reflective layer has an opening portion therein.
- 8. (previously amended) A liquid crystal device according to Claim 6, wherein the active element is a TFD.
  - 9. (previously amended) A liquid crystal device comprising:
  - a first substrate;
  - a second substrate disposed so as to oppose the first substrate;
  - a color layer provided on the first substrate;
- an insulating film provided on the color layer and comprising  $Ta_2O_5$  as a primary component; and
- a conductive film having a property of transmitting light provided on the insulating film.

- 10. (previously amended) A liquid crystal device according to Claim 9, wherein the insulating film further comprises at least one of ZrO<sub>2</sub>, TiO<sub>2</sub>, and SiO<sub>2</sub> as a component.
- 11. (previously amended) A liquid crystal device according to Claim 10, wherein, when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 12. (previously amended) A liquid crystal device according to Claim 11, wherein  $\lambda$  is 550 nm.
- 13. (previously amended) A liquid crystal device according to Claim 9, further comprising a transparent resin film provided between the color layer and the insulating film.
- 14. (previously amended) A liquid crystal device according to Claim 9, further comprising a reflective film provided between the color layer and the first substrate.
- 15. (previously amended) A liquid crystal device according to Claim 9, further comprising an underlying layer provided on the second substrate and composed of a

material substantially identical to that for the insulating film, and an active element provided on the underlying layer.

- 16. (previously amended) A liquid crystal device according to Claim 14, wherein the reflective layer has an opening portion therein.
- 17. (previously amended) A liquid crystal device according to Claim 15, wherein the active element is a TFD.
  - 18. (previously amended) A liquid crystal device comprising:

an insulating film comprising at least one of Ta<sub>2</sub>O<sub>5</sub>, ZrO<sub>2</sub>, and TiO<sub>2</sub> as a primary component; and

a conductive film having a property of transmitting light provided on the insulating film.

- 19. (previously amended) A liquid crystal device according to Claim 18, wherein, when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 20. (previously amended) A liquid crystal device according to Claim 19, wherein  $\lambda$  is 550 nm.

- 21. (previously amended) A liquid crystal device comprising:
- a first substrate;
- a second substrate disposed so as to oppose the first substrate;
- a color layer provided on the first substrate;

an insulating film provided on the color layer, having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a conductive film provided on the insulating film, having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

- 22. (previously amended) A liquid crystal device according to Claim 21, wherein, when an optional wavelength in the visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 23. (Currently amended) A liquid crystal device <u>according to Claim 1 wherein</u> comprising:

an the insulating film having has a refractive index of 1.6 to 2.0 in a visible wavelength region and a thickness of 10 nm to 100 nm; and

a the conductive film provided on the insulating film, having has a property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

- 24. (previously amended) A liquid crystal device according to Claim 23, wherein, when an optional wavelength in the visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
  - 25. (previously amended) A color filter substrate comprising: a substrate;
  - a color layer provided on the substrate;

an insulating film provided on the color layer and comprising one of  $Ta_2O_5$ ,  $ZrO_2$ , and  $TiO_2$  as a primary component; and

a conductive film having a property of transmitting light provided on the insulating film.

- 26. (previously amended) A color filter substrate according to Claim 25, wherein, when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 27. (previously amended) A color filter substrate according to Claim 26, wherein  $\lambda$  is 550 nm.

- 28. (previously amended) A color filter substrate according to Claim 25, further comprising a transparent resin film provided between the color layer and the insulating film.
- 29. (previously amended) A color filter substrate according to Claim 25, further comprising a reflective film provided between the color layer and the first substrate.
- 30. (previously amended) A color filter substrate according to Claim 29, wherein the reflective layer has an opening portion therein.
  - 31. (previously amended) A color filter substrate comprising:
  - a substrate;
  - a color layer provided on the substrate;
- an insulating film provided on the color layer and comprising  $Ta_2O_5$  as a primary component; and

a conductive film having a property of transmitting light provided on the insulating film.

32. (previously amended) A color filter substrate according to Claim 31, wherein the insulating film further comprises at least one of ZrO<sub>2</sub>, TiO<sub>2</sub>, and SiO<sub>2</sub> as a component.

- 33. (previously amended) A color filter substrate according to Claim 32, wherein, when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 34. (previously amended) A color filter substrate according to Claim 33, wherein  $\lambda$  is 550 nm.
- 35. (previously amended) A color filter substrate according to Claim 31, further comprising a transparent resin film provided between the color layer and the insulating film.
- 36. (previously amended) A color filter substrate according to Claim 31, further comprising a reflective film provided between the color layer and the first substrate.
- 37. (previously amended) A liquid crystal device according to Claim 36, wherein the reflective layer has an opening portion therein.
  - 38. (previously amended) A color filter substrate comprising:
  - a substrate;
  - a color layer provided on the substrate;

an insulating film provided on the color layer, having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a conductive film provided on the insulating film, having the property of transmitting light, a refractive index of 1.8 to 1.9, and a thickness of 100 nm to 300 nm.

- 39. (previously amended) A color filter substrate according to Claim 38, wherein, when an optional wavelength in the visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 40. (previously amended) A method for manufacturing a liquid crystal device, comprising:

a step of forming a color layer on a first substrate;

a step of forming an insulating film on the color layer, the insulating film comprising at least one of Ta<sub>2</sub>O<sub>5</sub>, ZrO<sub>2</sub>, and TiO<sub>2</sub> as a primary component;

a step of forming a conductive film having a property of transmitting light on the insulating film; and

a step of patterning the conductive film by using an alkaline solution.

41. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, wherein the insulating film and the conductive film are formed so that when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a

sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.

- 42. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising a step of forming a transparent resin film on the color layer.
- 43. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising a step of forming a reflective film on the first substrate.
- 44. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising: a step of forming an underlying layer on a second substrate, the underlying layer comprising a material substantially identical to that for the insulating film; and a step of forming an active element on the underlying layer.
- 45. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 43, further comprising a step of forming an opening portion in the reflective film.

- 46. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, wherein the insulating film is formed by vapor phase film-forming means.
- 47. (previously amended) A method for manufacturing a liquid crystal device, comprising:
  - a step of forming a color layer on a substrate;
- a step of forming an insulating film on the color layer, the insulating film comprising  $Ta_2O_5$  as a primary component and at least one of  $ZrO_2$ ,  $TiO_2$ , and  $SiO_2$  as a component;
- a step of forming a conductive film having a property of transmitting light on the insulating film; and
  - a step of patterning the conductive film by using an alkaline solution.
- 48. (previously amended) A method for manufacturing a liquid crystal device, comprising:
  - a step of forming a color layer on a substrate;
- a step of forming an insulating film on the color layer, the insulating film having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and
- a step of forming a conductive film on the insulating film, the conductive film having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

49. (previously amended) A method for manufacturing a color filter substrate, comprising:

a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film comprising at least one of Ta<sub>2</sub>O<sub>5</sub>, ZrO<sub>2</sub>, and TiO<sub>2</sub> as a primary component;

a step of forming a conductive film having a property of transmitting light on the insulating film; and

a step of patterning the conductive film by using an alkaline solution.

- 50. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, wherein the insulating film and the conductive film are formed so that when an optional wavelength in a visible wavelength region is represented by  $\lambda$ , a sum of an optical thickness of the insulating film and the optical thickness of the conductive film is substantially equal to a product of  $\lambda/2$  and a natural number.
- 51. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, further comprising a step of forming a transparent resin film on the color layer.
- 52. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, further comprising a step of forming a reflective film on the substrate.

- 53. (previously amended) A method for manufacturing a color filter substrate according to Claim 52, further comprising a step of forming an opening portion in the reflective film.
- 54. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, wherein the insulating film is formed by vapor phase film-forming means.
- 55. (previously amended) A method for manufacturing a color filter substrate, comprising:

a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a step of forming a conductive film on the insulating film; the conductive film having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.